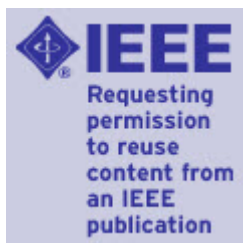




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Title: An Energy-Efficient Tensile-Strained Ge/InGaAs TFET 7T SRAM Cell Architecture for Ultralow-Voltage Applications

Author: Jheng-Sin Liu

Publication: Electron Devices, IEEE Transactions on

Publisher: IEEE

Date: May 2017

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Title: Performance Evaluation of Novel Strain-Engineered Ge-InGaAs Heterojunction Tunnel Field-Effect Transistors

Author: Jheng-Sin Liu

Publication: Electron Devices, IEEE Transactions on

Publisher: IEEE

Date: Oct. 2015

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Author: Jheng-Sin Liu, Michael Clavel,
Mantu K. Hudait

Publication: Applied Materials

Publisher: American Chemical Society

Date: Dec 1, 2015

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Author:

Jheng-Sin Liu, Yan Zhu, Patrick
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Publication: Applied Materials

Publisher: American Chemical Society

Date: Feb 1, 2015

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